Attorney Docket No. 7701
Customer Number: 49459

Amendments to the Specification

Please replace the paragraph beginning on page 2, line 18, with the following revised paragraph.

Accordingly, there is an ongoing need for methods of inhibiting corrosion of copper plated or metallized surfaces and circuits in semiconductor devices that ~~incorporates~~ incorporate precise control of corrosion inhibitor concentration to ensure that [[a]] effective corrosion inhibition is maintained throughout the manufacturing process without overdosing of inhibitor.

Please replace the paragraph beginning on page 10, line 4, with the following revised paragraph.

The analysis can be conducted ~~intermittantly~~ intermittently, in which case a sample of the aqueous fluid is removed from the system for analysis or alternatively, a spectrofluorometer can be installed on-line for conducting the triazole analysis and dosage control at the desired intervals or continuously.

Please replace the paragraph beginning on page 10, line 7, with the following revised paragraph.

A dual monochromator spectrofluorometer can be used for a fluorimetric analysis conducted on an intermittent basis and for on-line and/or continuous fluorescence regulating. Portable or compact fluorometers equipped with appropriate excitation and emission filters and quartz flow through cells are commercially available, for instance from ~~Ondeo~~ Nalco Company, Naperville, IL.

Please replace the paragraph beginning on page 11, line 23, with the following revised paragraph.

A preferred monitoring and control means is the TRASAR® Xe-2 Controller, available from ~~Ondeo~~ Nalco Company, Naperville, IL.

Please replace the paragraph beginning on page 13, line 9, with the following revised paragraph.

As discussed herein, the aqueous treating fluid used in semiconductor device manufacturing processes comprises ultrapure water. In order to maintain the integrity of the manufacturing process, it is imperative that no impurities be released ~~in-to~~ into the aqueous treating fluid from the flowcell. The chemical compatibility of the fluorometer flowcell of this invention with ultrapure water is shown in Table 4.

Please replace the ABSTRACT with the following revised ABSTRACT.

[[An]] A treatment bath for use in the manufacture of copper plated or metallized semiconductor devices and a method of inhibiting corrosion of copper plated or metallized surfaces and circuitry in the semiconductor devices immersed in an aqueous fluid in a treatment bath comprising adding to the aqueous fluid an effective corrosion inhibiting amount of one or more aromatic triazole corrosion inhibitors; fluorometrically monitoring the concentration of aromatic triazole corrosion inhibitors in the aqueous fluid; and adding additional aromatic triazole corrosion inhibitor to the aqueous fluid to maintain an effective corrosion inhibiting concentration of the aromatic triazole corrosion inhibitor in the aqueous fluid.